KSDT

Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[WeD3] Computational Lithography & Mask

Session Date	November 12 (Wed.), 2025
Session Time	16:05-17:45
Session Room	Room D (Sidney Room, 2F)

[WeD3-1] [Invited] 16:05-16:35

EUV and High-NA EUV Patterning for DRAM Scaling: Challenges and Opportunities

Jeonghoon Lee (imec, Belgium)

[WeD3-2] [Invited] 16:35-16:55

From Molecular Simulations to Artificial Intelligence for Advanced Patterning Materials Designs

Su-Mi Hur (Chonnam Nat'l Univ., Korea)

[WeD3-3] 16:55-17:10

Pioneering Carboxylated Zirconium Oxo Cluster Resist for Precision Nanoscale Patterning

Seong-Ji Ha, Bo Kyu Kwon, Jinyoung Lee, and Ji-Hyun Jang (UNIST, Korea)

[WeD3-4] [Invited] 17:10-17:30

MBM-4000: Electron Multi-Beam Mask Writer for Advanced Mask Making

Rieko Nishimura, Hiroshi Matsumoto, Kenichi Yasui, Tomoo Motosugi, Hayato Kimura, and Yoshinori Kojima (NuFlare Technology, Inc., Japan)

[WeD3-5] 17:30-17:45

Contamination Control Strategies in Next-Generation EUV Pods

Elson Tu, Asheesh Nautiyal, and Chiaho Chuang (Gudeng Precision Industry Co., Ltd., Taiwan)